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wave is turned on and off repeatedly, wherein a turn-off period is an alleviation period necessary to alleviate a vibration of the thing caused by applying said ultrasonic wave to the thing.

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2. (Amended) The ultrasonic washing method according to claim 1, wherein said ultrasonic wave is superimposed on a pulsed carrier wave.

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5. (Amended) The ultrasonic washing method according to claim 2, wherein a duty ratio of the carrier wave is 80% or less.

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6. (Amended) A washing method comprising:
a first step of washing a thing to be washed by applying a first ultrasonic wave, and
a second step of washing the thing by applying a second ultrasonic wave, wherein said first ultrasonic wave and said second ultrasonic wave are alternatively applied to the thing to alleviate a vibration caused by applying one of said first ultrasonic wave and said second ultrasonic wave to the thing.

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7. (Twice Amended) The washing method according to claim 6, wherein said first ultrasonic wave and said second ultrasonic wave are applied to the thing to be washed at predetermined time intervals, and the predetermined time intervals are intervals necessary to alleviate a vibration of the thing caused by applying said first ultrasonic wave and said second ultrasonic wave to the thing.

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8. (Amended) The washing method according to claim 6, wherein an oscillation frequency of each of said first and second ultrasonic waves is 0.6 MHz or higher.

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12. (Amended) The washing method according to claim 9, wherein an oscillation frequency of each of said first and second ultrasonic waves is 0.6 MHz or higher.

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19. (Amended) The method according to claim 1, wherein said ultrasonic wave is turned on and off repeatedly at specific time intervals, and the specific time intervals are intervals necessary to alleviate a vibration of the thing caused by applying said ultrasonic wave to the thing.

20. (Amended) The method according to claim 7, wherein said first ultrasonic wave and said second ultrasonic wave are repeated at a specific time interval and the specific time interval is an interval necessary to alleviate a vibration of the thing caused by applying said first ultrasonic wave and said second ultrasonic wave to the thing.

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--24. (New) An ultrasonic washing method of washing a thing to be washed by supplying ultrasonic-wave-applied cleaning fluid to the thing, said ultrasonic washing method comprising applying an ultrasonic wave to a cleaning fluid in such a manner that said ultrasonic wave is turned on and off repeatedly, wherein a turn-off period is an alleviation period necessary to alleviate a vibration of a silicon crystal caused by applying said ultrasonic wave to the thing.

25. (New) The ultrasonic washing method according to claim 24, wherein said ultrasonic wave is superimposed on a pulsed carrier wave.

- SMB/1*
26. (New) The ultrasonic washing method according to claim 25, wherein a frequency of said carrier wave is lower than an oscillation frequency of said ultrasonic wave.
- BS*
27. (New) The ultrasonic washing method according to claim 24, wherein an oscillation frequency of said ultrasonic wave is 0.6 MHz or higher.
28. (New) The ultrasonic washing method according to claim 25, wherein a duty ratio of the carrier wave is 80% or less.
29. (New) An ultrasonic washing method of washing a thing to be washed by supplying ultrasonic-wave-applied cleaning fluid to the thing, said ultrasonic washing method comprising applying an ultrasonic wave to a cleaning fluid in such a manner that said ultrasonic wave is turned on and off repeatedly, wherein a turn-off period is an alleviation period necessary to alleviate a vibration of a structure at a surface of a silicon crystal caused by applying said ultrasonic wave to the thing.
30. (New) The ultrasonic washing method according to claim 29, wherein said ultrasonic wave is superimposed on a pulsed carrier wave.
31. (New) The ultrasonic washing method according to claim 30, wherein a frequency of said carrier wave is lower than an oscillation frequency of said ultrasonic wave.
32. (New) The ultrasonic washing method according to claim 29, wherein an oscillation frequency of said ultrasonic wave is 0.6 MHz or higher.

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33. (New) The ultrasonic washing method according to claim 30, wherein a duty ratio of the carrier wave is 80% or less.

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34. (New) A washing method comprising:
a first step of washing a thing to be washed by applying a first ultrasonic wave, and
a second step of washing the thing by applying a second ultrasonic wave, wherein said first ultrasonic wave and said second ultrasonic wave are alternatively applied to the thing to alleviate a vibration of a silicon crystal caused by applying one of said first ultrasonic wave and said second ultrasonic wave to the thing.

35. (New) The washing method according to claim 34, wherein said first ultrasonic wave and said second ultrasonic wave are applied to the thing to be washed at predetermined time intervals, and the predetermined time intervals are intervals necessary to alleviate the vibration of the silicon crystal caused by applying said first ultrasonic wave and said second ultrasonic wave to the thing.

36. (New) The washing method according to claim 34, wherein an oscillation frequency of each of said first and second ultrasonic waves is 0.6 Mhz or higher.

37. (New) The washing method according to claim 34, wherein said first ultrasonic wave differs from said second ultrasonic wave in any one of phase, wavelength, and amplitude.

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38. (New) A washing method comprising:

a first step of washing a thing to be washed by applying a first ultrasonic wave; and
a second step of washing the thing by applying a second ultrasonic wave, wherein said
first ultrasonic wave and said second ultrasonic wave are alternatively applied to the thing to
alleviate a vibration of a structure at a surface of a silicon crystal caused by applying one of said
first ultrasonic wave and said second ultrasonic wave to the thing.

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39. (New) The washing method according to claim 38, wherein said first ultrasonic
wave and said second ultrasonic wave are applied to the thing to be washed at predetermined
time intervals, and the predetermined time intervals are intervals necessary to alleviate the
vibration of the structure caused by applying said first ultrasonic wave and said second ultrasonic
wave to the thing.

40. (New) The washing method according to claim 38, wherein an oscillation frequency
of each of said first and second ultrasonic waves is 0.6 MHz or higher.

41. (New) The washing method according to claim 38, wherein said first ultrasonic
wave differs from said second ultrasonic wave in any one of phase, wavelength, and amplitude.

42. (New) An ultrasonic washing method of washing a thing to be washed by supplying
ultrasonic-wave-applied cleaning fluid to the thing, said ultrasonic washing method comprising
applying an ultrasonic wave to a cleaning fluid in such a manner that said ultrasonic wave is
turned on and off repeatedly, wherein a turn-off period is an alleviation period necessary to